

| L Number | Hits | Search Text | DE | Time stamp |
|----------|---------|---|---|------------------|
| 1 | 2 | ("20020086222").FN. | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/12/04 12:45 |
| 2 | 2 | jp-04136854-\$.did. | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/12/04 13:07 |
| 3 | 419602 | mask photomask photo-mask reticle | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/12/04 13:07 |
| 4 | 11816 | krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter)) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/12/04 13:07 |
| 5 | 322491 | photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/12/04 13:08 |
| 6 | 421918 | photoresist photo-resist resist | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/12/04 13:08 |
| 7 | 4696 | MOMOSE-SATOSHI-.in. MOMOSE-SATOKO-.in. MOMOSE-S-.in. ARAI-TADASHI-.in. ARAI-TADASHI-PROF-DR-.in. | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/12/04 13:08 |
| 8 | 146 | ARAKI-TSUTOMU-.in. yamaguchi-osamu-.in. (MOMOSE-SATOSHI-.in. MOMOSE-SATOKO-.in. MOMOSE-S-.in. ARAI-TADASHI-.in. ARAI-TADASHI-PROF-DR-.in. | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/12/04 13:08 |
| 9 | 7 | ARAKI-TSUTOMU-.in. yamaguchi-osamu-.in.) and (mask photomask photo-mask reticle) (MOMOSE-SATOSHI-.in. MOMOSE-SATOKO-.in. MOMOSE-S-.in. ARAI-TADASHI-.in. ARAI-TADASHI-PROF-DR-.in. | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/12/04 13:12 |
| 10 | 2621548 | ARAKI-TSUTOMU-.in. yamaguchi-osamu-.in.) and (mask photomask photo-mask reticle) and (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) transmit\$7 transmission | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/12/04 13:11 |
| 11 | 5 | (MOMOSE-SATOSHI-.in. MOMOSE-SATOKO-.in. MOMOSE-S-.in. ARAI-TADASHI-.in. ARAI-TADASHI-PROF-DR-.in. ARAKI-TSUTOMU-.in. yamaguchi-osamu-.in.) and (mask photomask photo-mask reticle) and (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) and (transmit\$7 transmission) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/12/04 13:15 |
| 12 | 614196 | shade shield\$3 opaque | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/12/04 13:18 |
| 13 | 1332 | (mask photomask photo-mask reticle) with (((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near3 (shade shield\$3 opaque)) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/12/04 13:22 |

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| 14 | 4 | ((mask photomask photo-mask reticle) with (((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near3 (shade shield\$3 opaque))) with (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) with (transmit\$7 transmission) attenuat\$5 | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/12/04 13:25 |
| 15 | 233480 | | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/12/04 13:20 |
| 16 | 59 | (mask photomask photo-mask reticle) with (((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near3 attenuat\$5) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/12/04 13:23 |
| 17 | 1 | ((mask photomask photo-mask reticle) with (((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near3 attenuat\$5)) with (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) with (transmit\$7 transmission) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/12/04 13:24 |
| 18 | 19 | ((mask photomask photo-mask reticle) with (((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near3 (shade shield\$3 opaque))) ((mask photomask photo-mask reticle) with (((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near3 attenuat\$5))) with (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/12/04 13:28 |
| 19 | 31 | (mask photomask photo-mask reticle) with (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) with ((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) with (transmit\$7 transmission) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/12/04 13:35 |
| 20 | 77786 | 3.ti. | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/12/04 13:35 |
| 21 | 6397 | 430/5.ccls. | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/12/04 13:35 |
| 22 | 79647 | 3.ti. 430/5.ccls. | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/12/04 13:36 |
| 23 | 1 | (3.ti. 430/5.ccls.) and (((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) with (blank (quartz adj substrate)) with (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) with (transmit\$7 transmission)) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/12/04 13:49 |

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| 24 | 3338 | ((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) with (blank (quartz adj substrate)) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/12/04 14:36 |
| 26 | 8 | ((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) with (blank (quartz adj substrate))) same ((krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) with (transmit\$7 transmission)) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/12/04 13:43 |
| 27 | 243122 | (blank (quartz adj substrate)) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/12/04 13:49 |
| 28 | 32 | (photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) with (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) with (transmit\$7 transmission) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/12/04 13:51 |
| 29 | 9 | (3.ti. 430/5.ccls.) and ((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) with (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) with (transmit\$7 transmission)) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/12/04 13:52 |
| 30 | 15163 | ((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 polymer\$5 | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/12/04 13:55 |
| 31 | 0 | ((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 polymer\$5 with ((blank (quartz adj substrate))) with (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) with (transmit\$7 transmission) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/12/04 13:59 |
| 32 | 0 | ((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 polymer\$5 same ((blank (quartz adj substrate))) same (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) same (transmit\$7 transmission) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/12/04 14:00 |
| 33 | 2 | ((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 polymer\$5 with (mask photomask photo-mask reticle) with (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) with (transmit\$7 transmission) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/12/04 14:00 |
| 34 | 4 | ((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 polymer\$5 same (mask photomask photo-mask reticle) same (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) same (transmit\$7 transmission) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/12/04 14:22 |

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| 35 | 411 | ((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) same (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) same (transmit\$7 transmission) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/12/04 14:22 |
| 36 | 94 | (3.ti. 430/5.ccls.) and ((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) same (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) same (transmit\$7 transmission)) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/12/04 14:28 |
| 37 | 722932 | "%" | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/12/04 14:28 |
| 38 | 781142 | percent percentage | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/12/04 14:28 |
| 39 | 1224949 | "%" (percent percentage) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/12/04 14:29 |
| 40 | 10929 | (transmit\$7 transmission) near2 ("%" (percent percentage)) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/12/04 14:30 |
| 41 | 19 | ((transmit\$7 transmission) near2 ("%" (percent percentage))) with (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/12/04 14:30 |
| 42 | 807 | ((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (blank (quartz adj substrate)) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/12/04 14:36 |
| 43 | 71511 | ((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (pattern (shade shield\$3 opaque) attenuat\$5) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/12/04 14:37 |
| 44 | 101 | ((((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (blank (quartz adj substrate))) ((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (pattern (shade shield\$3 opaque) attenuat\$5))) same (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) same ("%" (percent percentage)) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/12/04 14:44 |

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| 45 | 9 | (3.ti. 430/5.ccls.) and ((((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (blank (quartz adj substrate))) ((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (pattern (shade shield\$3 opaque) attenuat\$5))) same (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) same ("% (percent percentage))) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/12/04 14:43 |
| 46 | 92 | ((((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (blank (quartz adj substrate))) ((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (pattern (shade shield\$3 opaque) attenuat\$5))) same (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) same ("% (percent percentage))) not ((3.ti. 430/5.ccls.) and ((((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (blank (quartz adj substrate))) ((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (pattern (shade shield\$3 opaque) attenuat\$5))) same (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) same ("% (percent percentage)))) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/12/04 14:44 |
| 47 | 86 | ((((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (blank (quartz adj substrate))) ((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (pattern (shade shield\$3 opaque) attenuat\$5))) same (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) same ("% (percent percentage)))) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/12/04 14:44 |

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| 48 | 81 | ((((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (blank (quartz adj substrate))) ((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (pattern (shade shield\$3 opaque) attenuat\$5))) same (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) same ("%") not ((3.ti. 430/5.ccls.) and (((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (blank (quartz adj substrate))) ((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (pattern (shade shield\$3 opaque) attenuat\$5))) same (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) same ("% (percent percentage)))) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/12/04 14:45 |
| 49 | 110 | (((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (blank (quartz adj substrate))) ((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (pattern (shade shield\$3 opaque) attenuat\$5))) same (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) same ("% (percent percentage)))) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/12/04 14:45 |
| 50 | 105 | ((((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (blank (quartz adj substrate))) ((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (pattern (shade shield\$3 opaque) attenuat\$5))) same (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) same ((transmit\$7 transmission)) not ((3.ti. 430/5.ccls.) and (((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (blank (quartz adj substrate))) ((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (pattern (shade shield\$3 opaque) attenuat\$5))) same (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) same ("% (percent percentage)))) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/12/04 14:58 |

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| 51 | 321 | ((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (shade shield\$3 opaque) near2 ((mask photomask photo-mask reticle) ((blank (quartz adj substrate)))) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/12/04 15:01 |
| 52 | 9 | ((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 attenuat\$5 near2 ((mask photomask photo-mask reticle) ((blank (quartz adj substrate)))) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/12/04 15:06 |
| 53 | 19 | ((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (shade shield\$3 opaque) near2 ((mask photomask photo-mask reticle) ((blank (quartz adj substrate)))) same (transmit\$7 transmission) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/12/04 15:04 |
| 54 | 62 | ((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (shade shield\$3 opaque) near2 ((mask photomask photo-mask reticle) ((blank (quartz adj substrate)))) and (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) and (transmit\$7 transmission) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/12/04 15:24 |
| 55 | 186 | ((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (half adj tone shift\$3) near2 ((mask photomask photo-mask reticle) ((blank (quartz adj substrate)))) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/12/04 15:36 |
| 56 | 48 | ((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (half adj tone shift\$3) near2 ((mask photomask photo-mask reticle) ((blank (quartz adj substrate)))) and (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) and (transmit\$7 transmission) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/12/04 15:12 |
| 57 | 8 | ((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (shade shield\$3 opaque) near2 ((mask photomask photo-mask reticle) ((blank (quartz adj substrate)))) and (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) and (transmit\$7 transmission)) and (((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (half adj tone shift\$3) near2 ((mask photomask photo-mask reticle) ((blank (quartz adj substrate)))) and (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) and (transmit\$7 transmission)) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/12/04 15:15 |

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| 58 | 102 | (((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (shade shield\$3 opaque) near2 ((mask photomask photo-mask reticle) ((blank (quartz adj substrate))))) and (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) and (transmit\$7 transmission)) (((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (half adj tone shift\$3) near2 ((mask photomask photo-mask reticle) ((blank (quartz adj substrate))))) and (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) and (transmit\$7 transmission))) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/12/04 15:15 |
| 59 | 94 | (((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (shade shield\$3 opaque) near2 ((mask photomask photo-mask reticle) ((blank (quartz adj substrate))))) and (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) and (transmit\$7 transmission)) (((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (half adj tone shift\$3) near2 ((mask photomask photo-mask reticle) ((blank (quartz adj substrate))))) and (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) and (transmit\$7 transmission))) not (((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (shade shield\$3 opaque) near2 ((mask photomask photo-mask reticle) ((blank (quartz adj substrate))))) and (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) and (transmit\$7 transmission)) and (((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (half adj tone shift\$3) near2 ((mask photomask photo-mask reticle) ((blank (quartz adj substrate))))) and (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) and (transmit\$7 transmission))) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/12/04 15:16 |

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| 60 | 57 | ((((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (shade shield\$3 opaque) near2 ((mask photomask photo-mask reticle) ((blank (quartz adj substrate))))) and (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) and (transmit\$7 transmission)) (((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (half adj tone shift\$3) near2 ((mask photomask photo-mask reticle) ((blank (quartz adj substrate))))) and (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) and (transmit\$7 transmission))) not (((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (shade shield\$3 opaque) near2 ((mask photomask photo-mask reticle) ((blank (quartz adj substrate))))) and (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) and (transmit\$7 transmission)) and (((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (half adj tone shift\$3) near2 ((mask photomask photo-mask reticle) ((blank (quartz adj substrate))))) and (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) and (transmit\$7 transmission)))) and (3.ti. 430/5.ccls.) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/12/04 15:16 |
| 61 | 45 | (((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (shade shield\$3 opaque) near2 ((mask photomask photo-mask reticle) ((blank (quartz adj substrate))))) (((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (half adj tone shift\$3) near2 ((mask photomask photo-mask reticle) ((blank (quartz adj substrate))))) and ((krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) SAME (transmit\$7 transmission))) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/12/04 15:25 |
| 62 | 503 | ((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (half adj tone shift\$3 attenuat\$5 (shade shield\$3 opaque)) near2 ((mask photomask photo-mask reticle) ((blank (quartz adj substrate))))) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/12/04 16:13 |
| 63 | 792 | (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) with (transmit\$7 transmission) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/12/04 15:39 |

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| 64 | 0 | ((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (half adj tone shift\$3 attenuat\$5 (shade shield\$3 opaque)) near2 ((mask photomask photo-mask reticle) ((blank (quartz adj substrate))))) same ((krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) with (transmit\$7 transmission)) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/12/04 15:39 |
| 65 | 28 | ((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (half adj tone shift\$3 attenuat\$5 (shade shield\$3 opaque)) near2 ((mask photomask photo-mask reticle) ((blank (quartz adj substrate))))) and ((krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) with (transmit\$7 transmission)) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/12/04 15:56 |
| 68 | 3 | ((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (half adj tone shift\$3 attenuat\$5 (shade shield\$3 opaque)) near2 ((mask photomask photo-mask reticle) ((blank (quartz adj substrate))))) same (krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) same (transmit\$7 transmission) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/12/04 16:14 |
| 69 | 194 | ((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (half adj tone shift\$3 attenuat\$5) near2 ((mask photomask photo-mask reticle) ((blank (quartz adj substrate))))) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/12/04 16:14 |
| 70 | 29 | ((photosensitive photo-sensitive photo adj sensitive ((light radiation energy) near sensitive)) (photoresist photo-resist resist)) near2 (half adj tone shift\$3 attenuat\$5) near2 ((mask photomask photo-mask reticle) ((blank (quartz adj substrate))))) and ((krf (krypton adj (fluorine fluoride)) ("248" adj (nm nanometer nano-meter nano adj meter))) same (transmit\$7 transmission)) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2003/12/04 16:14 |